

## IN THE CLAIMS

Please amend the claims as follows:

21. The method of claim 20, wherein forming a performance circuit includes forming a CMOS configuration.
22. The method of claim 21, wherein coupling the protection circuit to the performance circuit includes coupling the protection circuit to a p-channel device of the CMOS configuration.
23. The method of claim 21, wherein forming a protection circuit includes forming a diode and coupling the protection circuit to the performance circuit includes coupling the diode to a p-channel device of the CMOS configuration.
24. The method of claim 20, wherein forming a protection circuit includes forming a unit diode, the unit diode comprised of a block of a doped region of the integrated circuit substrate occupying an area of the substrate sufficient to support a contact to the doped region, a junction region of the integrated circuit substrate surrounding the doped region, and a contact to the doped region.
25. The method of claim 20, a doped region being a first doped region of a first dopant in a well of the substrate, the well being doped with a first concentration of a second dopant and a junction region separating the first doped region from the well, wherein forming a protection circuit includes forming a third doped region in the well adjacent the junction region, the third doped region doped with a second concentration of the second dopant.
26. The method of claim 25, wherein forming a protection circuit includes forming a plurality of unit diodes.
27. The method of claim 20, wherein forming a performance circuit includes:
- Sub C1 Cont*
- Sub C2*
- Sub C1 Cont*

*BK*  
*well*  
*Sub*  
*cont*  
forming a unit transistor device having a drain region comprised of a doped region of the integrated circuit substrate occupying an area sufficient to support a contact to the doped region;

forming a gate region of the integrated circuit substrate surrounding the doped region; and

forming a contact to the doped region.

*for*  
*Sub*  
*El*  
*cont*  
29. The method of claim 28, wherein forming a performance circuit includes:  
forming a plurality of unit transistors.